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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Sato, et al.
Int'l Appl. No. : PCT/JP2003/016266
Int'l Filing Date : December 18, 2003
For : POSITIVE RESIST
COMPOSITION AND METHOD
OF FORMING RESIST PATTERN
Examiner : Unknown
Group Art Unit : Unknown

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination on the merits, please amend the present application.

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 7 of this paper.